



**Gleskova, Helena and Ma, E.Y. and Wagner, S. and Shen, D. (1996)
Flexible glass substrates with via holes for TFT backplanes. In: Digest of
technical papers. The Japan Society of Physics, Kobe, Japan, pp. 105-
108. ,**

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AM-LCD 96



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JAPAN CHAPTER

DIGEST OF TECHNICAL PAPERS

1996

INTERNATIONAL WORKSHOP ON
ACTIVE-MATRIX
LIQUID-CRYSTAL DISPLAYS
in conjunction with IDW'96

November 27-29, 1996
International Conference Center Kobe
Kobe, Japan

UB/TIB Hannover
116 026 758



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